



MEMC 98-1451/2554.1
PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application of Robert J. Falster, et al

Art Unit 1765

Serial No. 10/073,506

Filed February 11, 2002

Confirmation No. 6190

For THERMAL ANNEALING PROCESS FOR PRODUCING LOW DEFECT
DENSITY SINGLE CRYSTAL SILICON

Examiner Matthew A. Anderson

May 29, 2003

TO THE COMMISSIONER OF PATENTS,

SIR:

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SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

In accordance with 37 C.F.R. 1.97 and 1.98 and MPEP 609, and in compliance with the duty of disclosure set forth in 37 C.F.R. 1.56, applicants submit copies of the references listed on the attached PTO/SB/08A for consideration by the Patent and Trademark Office in the above-entitled application and to be made of record therein.

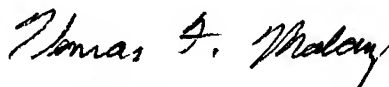
This application is a divisional of U.S. Application Serial No. 09/416,998, filed October 13, 1999. Pursuant to M.P.E.P. §609, Applicants are not submitting copies of Reference Nos. 1-40, 42, 45-61, 64-68, 70-91, 93-110, 112-126, 128-136 and 139-140, which were previously made of record in application Serial No. **09/416,998**. Applicants are not submitting copies of Reference Nos. 41, 43-44, 62-63, 69, 92, 111, 127 and 137-138, which were previously submitted with the Information Disclosure Statement filed on May 16, 2002.

Please note that there were several translations previously submitted with Application Serial No. 09/416,998, as well as new translations previously submitted in the present application, and Applicants make no representation as to accuracy or completeness of those translations.

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* A check in the amount of \$180.00 is enclosed to cover the fee specified in 37 CFR §1.17(p) for submission of this Supplemental Information Disclosure Statement.

Respectfully submitted,



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